

SUFELW
STOCKHOLM-UPPSALA CENTRE FOR
FREE ELECTRON LASER RESEARCH



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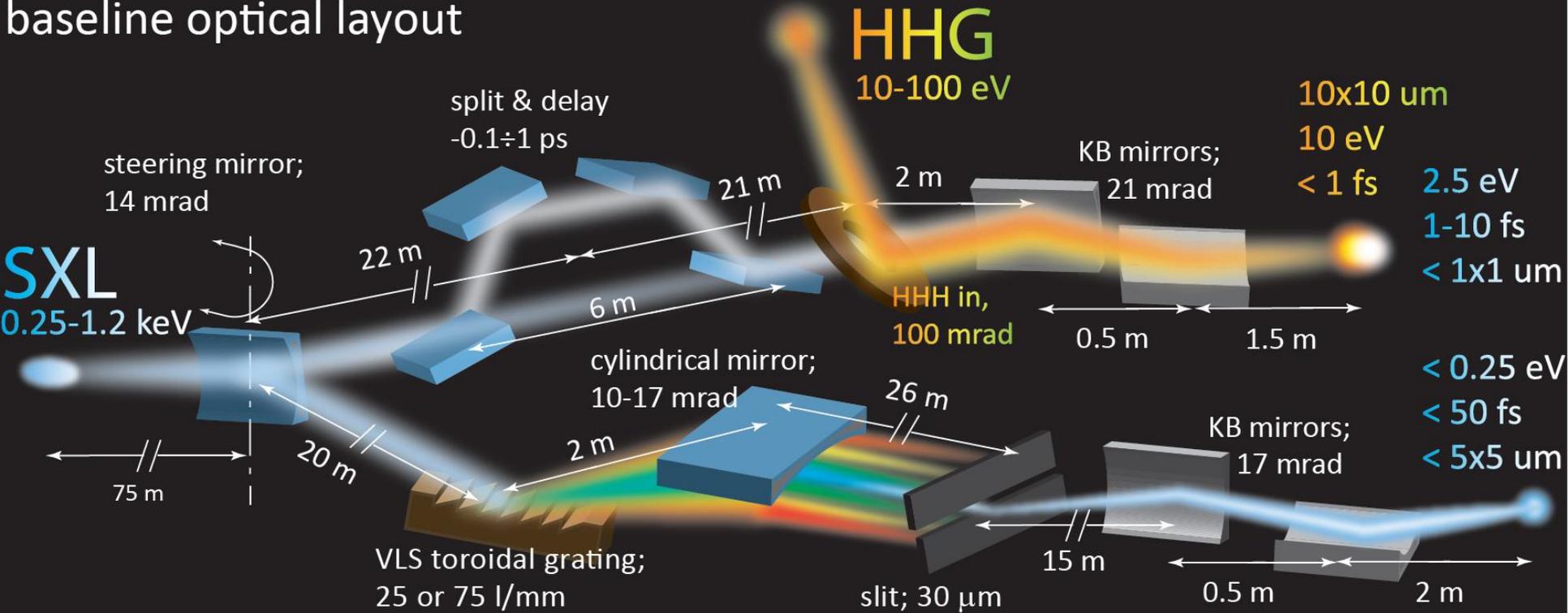
PHOTON BEAMLINES FOR SXL

Vitaliy Goryashko & Peter Salen

2020-11-30

Conceptual SXL layout

baseline optical layout



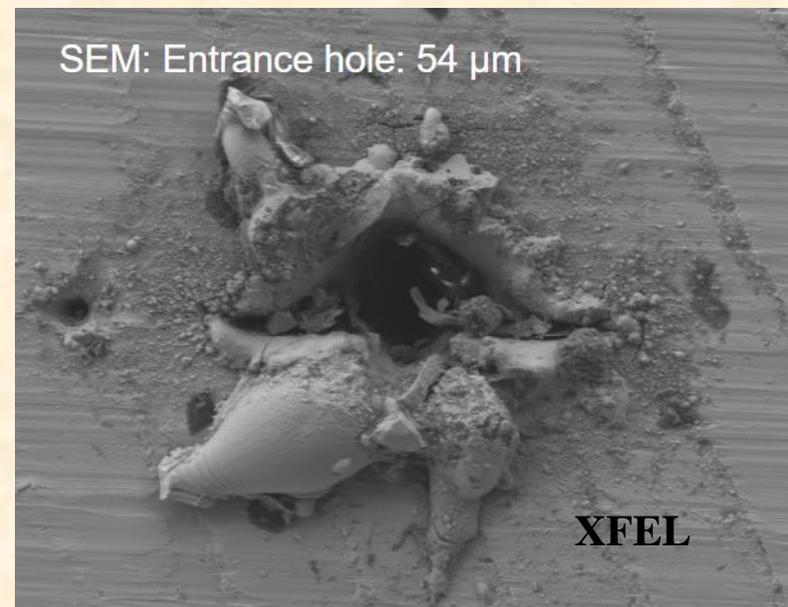
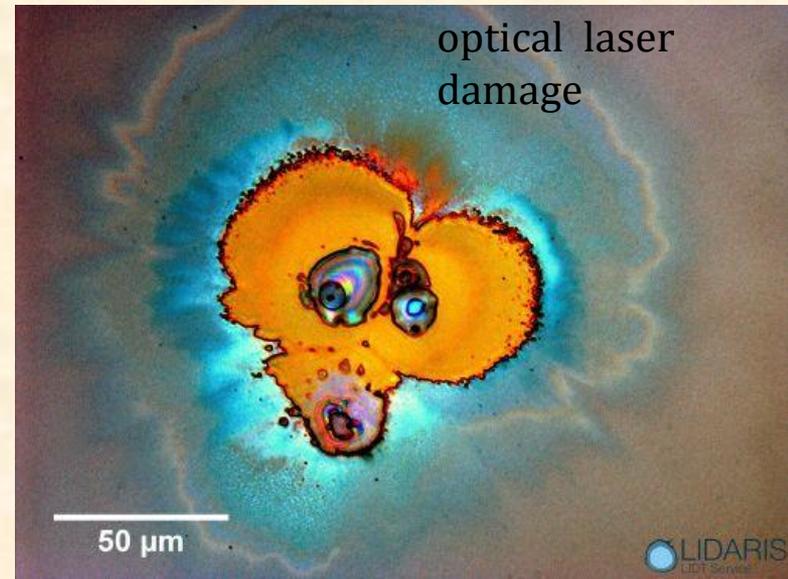
Key parts of the beamline:

- Pink (microscopy) and mono (spectroscopy) branches
- Focusing optics
- Monochromator (only for mono branch)
- Split & delay unit
- External lasers for pump-probe experiments



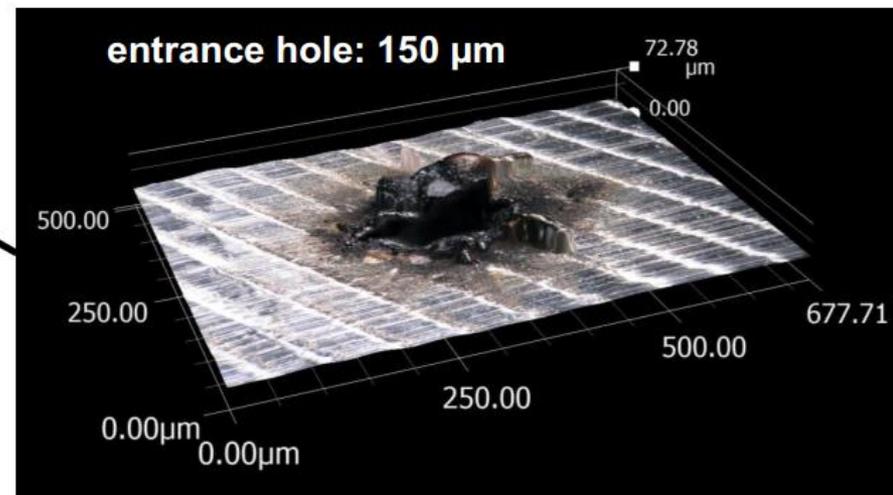
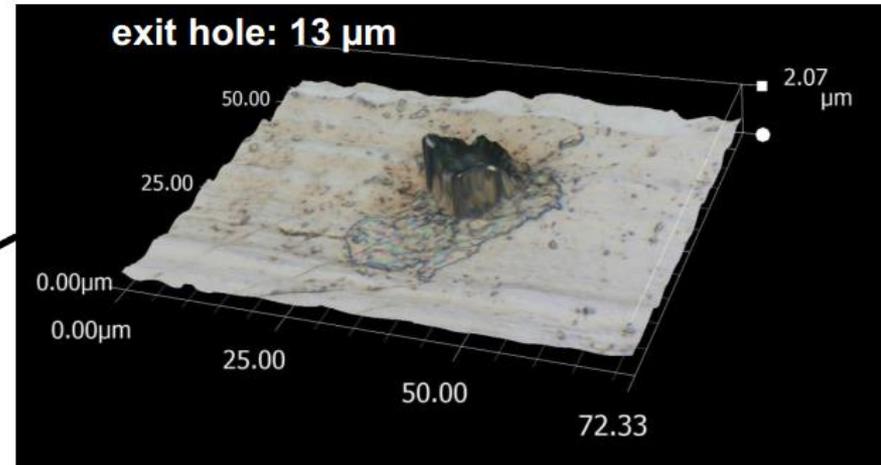
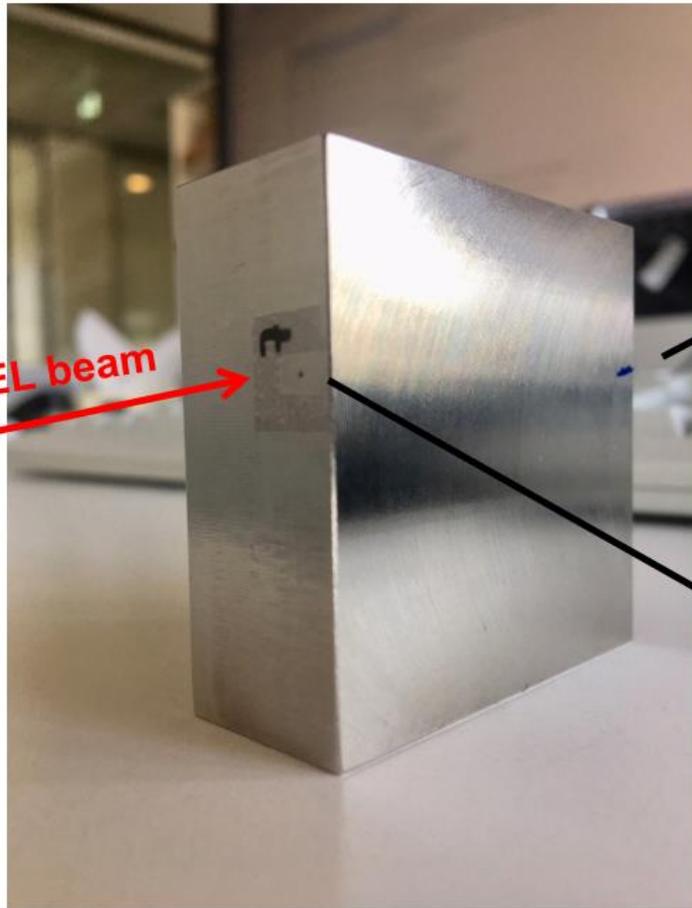
Optical damage of X-ray optics

- High-fluence FEL pulses can cause a **single-shot damage** of optical components .
- **Damage dose** ~ energy to raise the material's temperature from room temperature to its melting point.
- The LCLS beam drills steel at a rate of ~ mm/sec if the threshold is exceeded.
- Ablation speed ~ 10 um/shot at 1 mJ.
- The FEL beam must first be magnified via free-space diffraction.
- A wide range of materials such as B4C, Mo, Ru, Rh, W, and Pt on a Si substrate have been studied by the X-ray optics community.



European XFEL: example

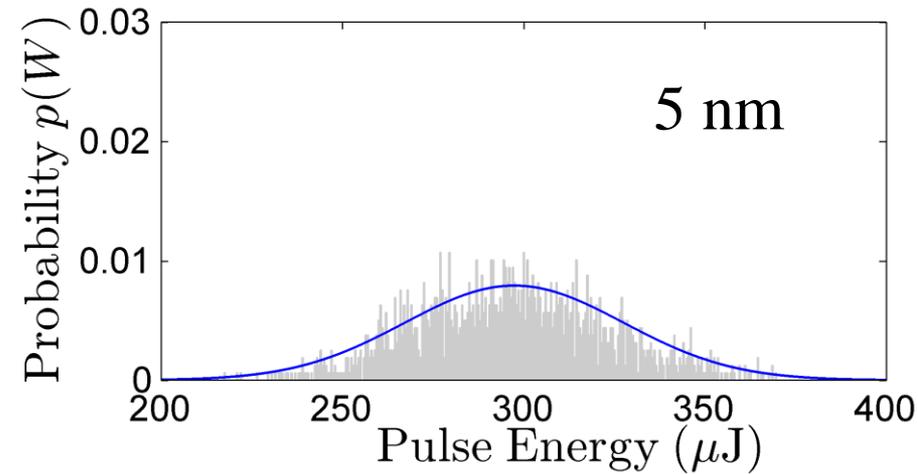
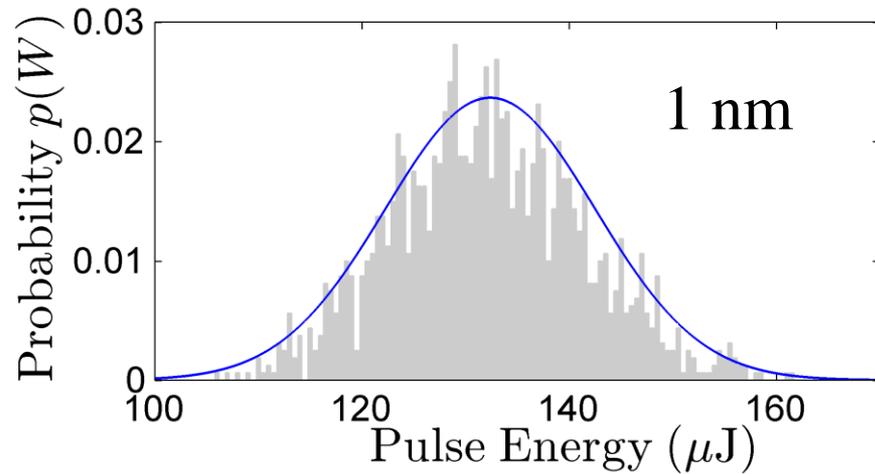
Drilling with XFEL beam through 50 mm of steel in 26 seconds



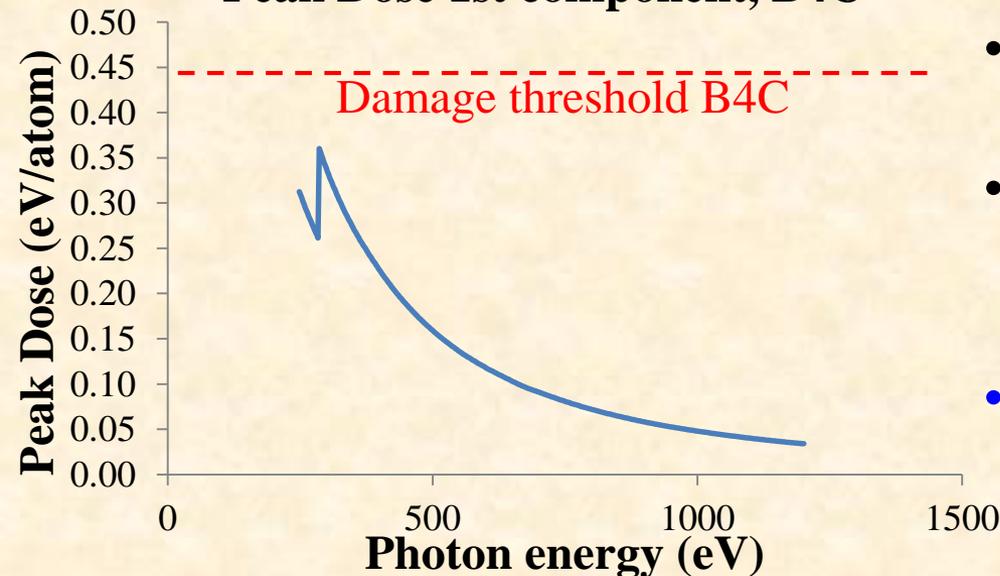
European XFEL

H. Sinn, A. Leuschner, F. Yang et al., European XFEL

Maximum FEL pulse energy

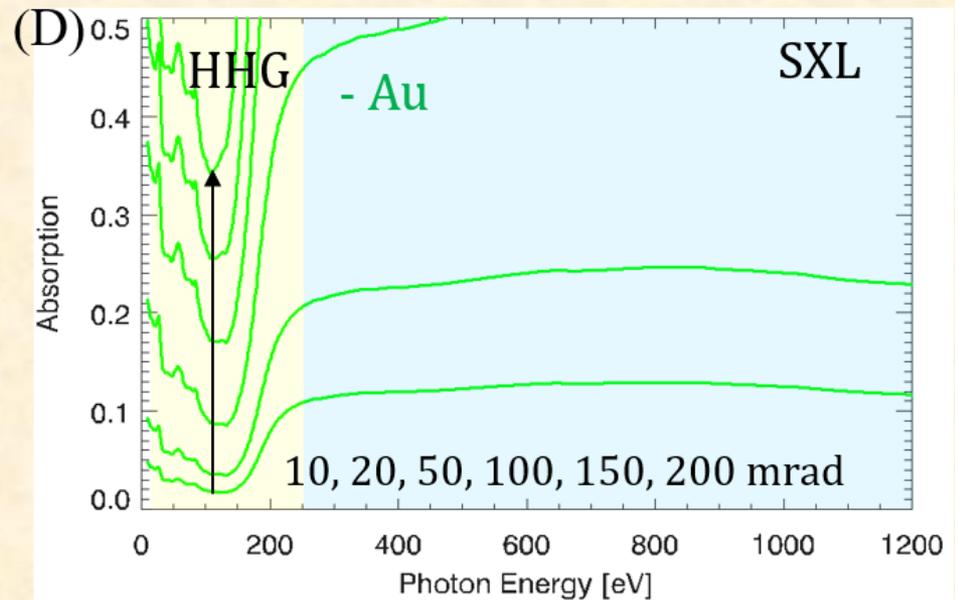
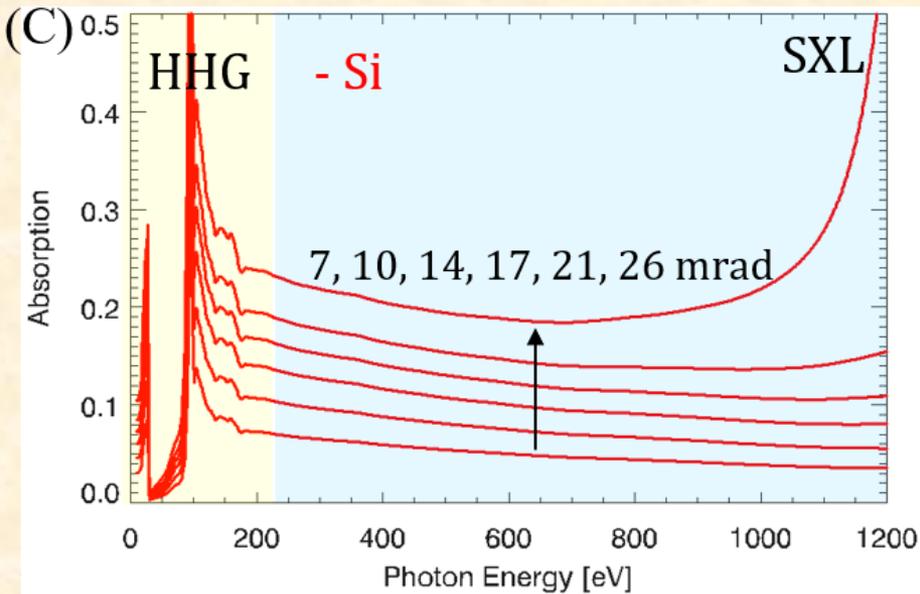
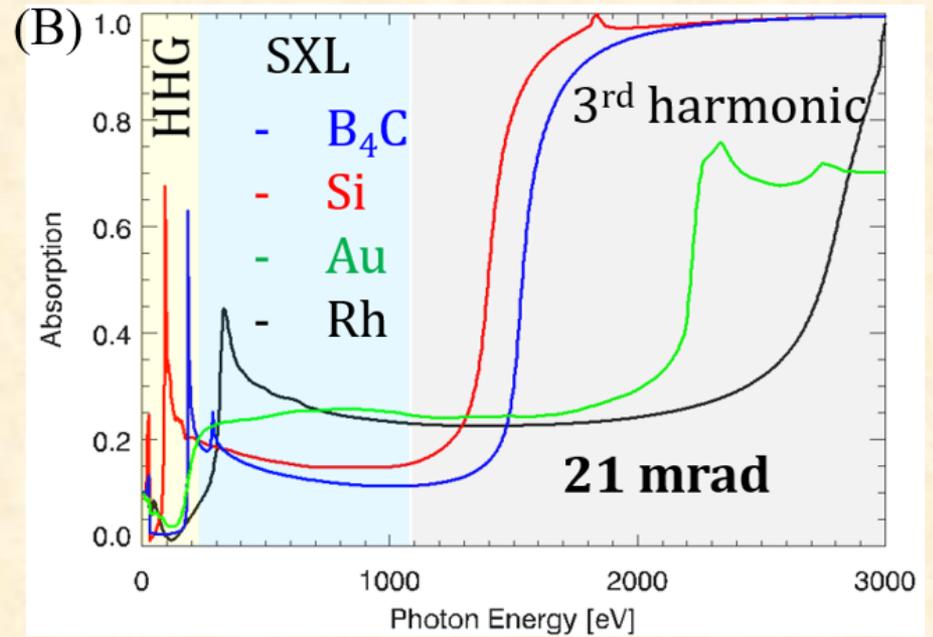
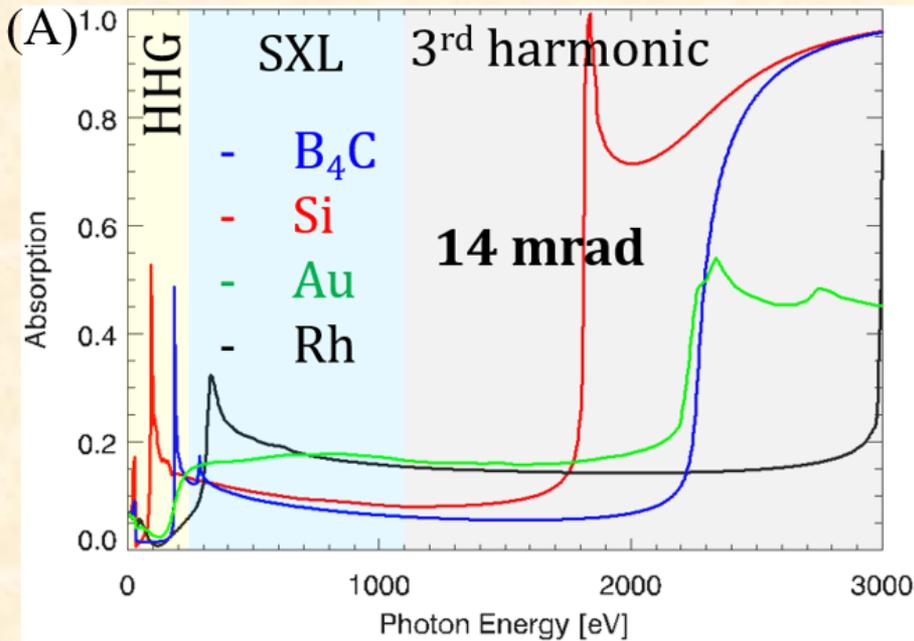


Peak Dose 1st component, B4C



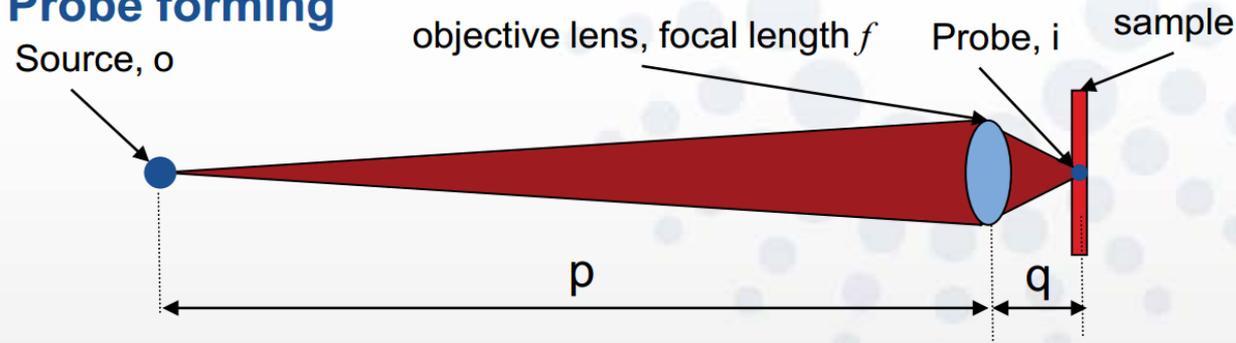
- SASE is a stochastic process with a Gaussian-like energy distribution.
- The uncertainty of S2E simulations is $\sim 20\%$. The margin for optical design is assumed to be 20%.
- For safe optical design, we assume 1.2 mJ at 1 nm and 4.3 mJ at 5 nm.

Mirror coating for SXL up to 3 keV



Focusing and beam size

Probe forming



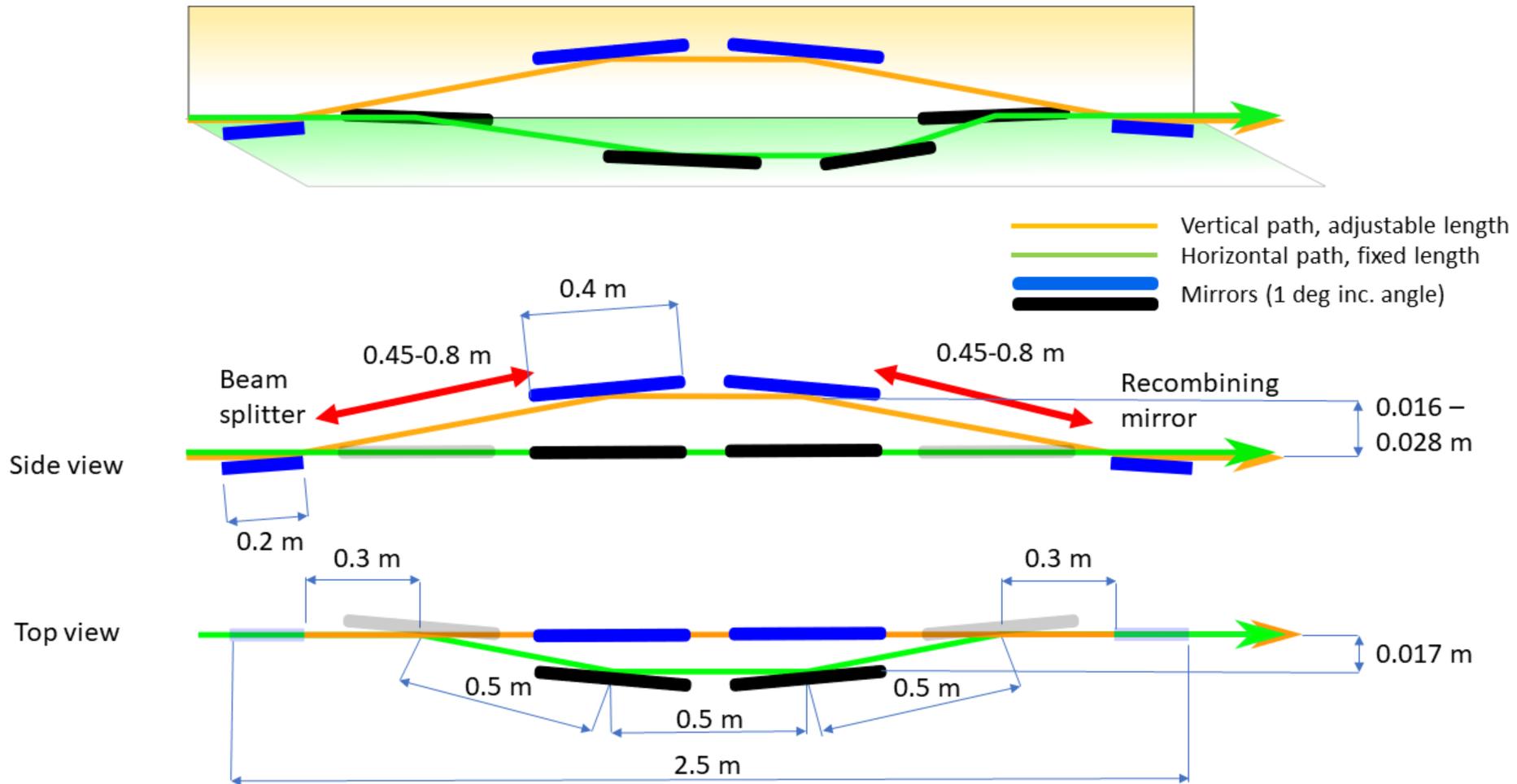
Thin lens	$\frac{1}{p} + \frac{1}{q} = \frac{1}{f}$
Magnification,	$M = \frac{i}{o} = \frac{q}{p}$
For fixed p ,	$M \uparrow \Rightarrow f \downarrow$

R. Barret, ESRF

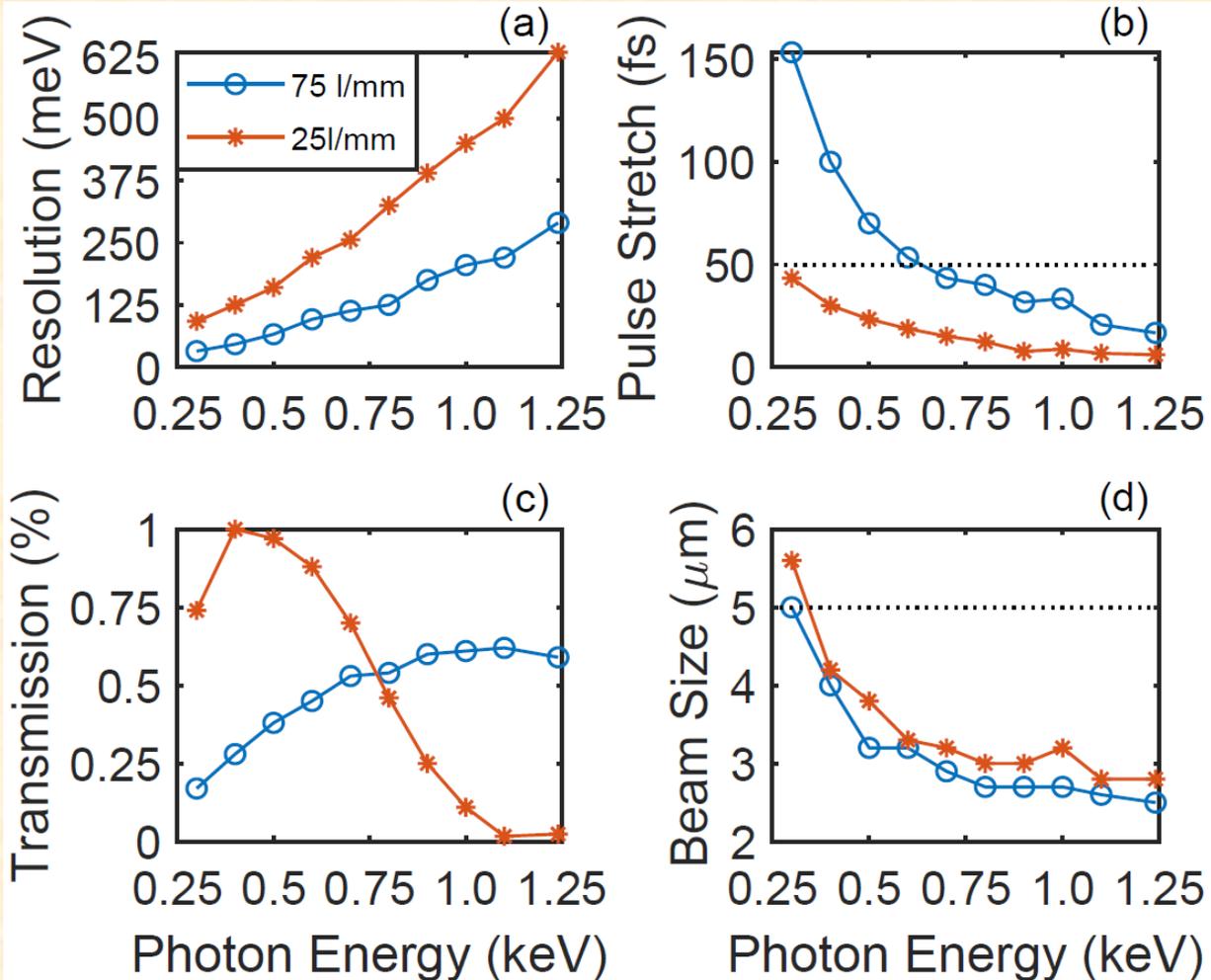
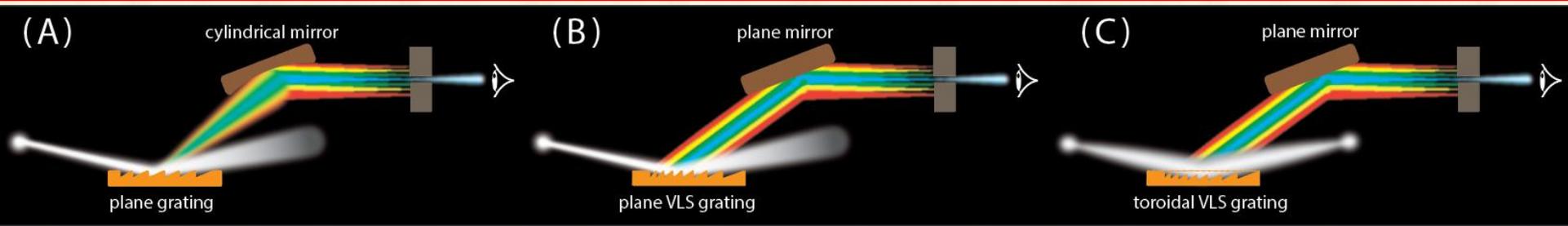
- FEL beam size $\sigma_0 \sim 20\text{-}50 \text{ }\mu\text{m}$
- desired beam size at the sample $\sigma'_0 \sim 0.5 \text{ }\mu\text{m}$
- required demagnification ~ 100
- if the exit arm ($\approx f$) equals 1 m, then the **entrance arm 100 m**
- for a real beam of light, the lens equation must account for diffraction

$$\frac{1}{p + z_0^2/(p - f)} + \frac{1}{q} = \frac{1}{f} \quad \sigma'_0 = \frac{\sigma_0 f}{\sqrt{(p - f)^2 + z_0^2}} \quad z_0 - \text{Rayleigh length}$$

Split & delay

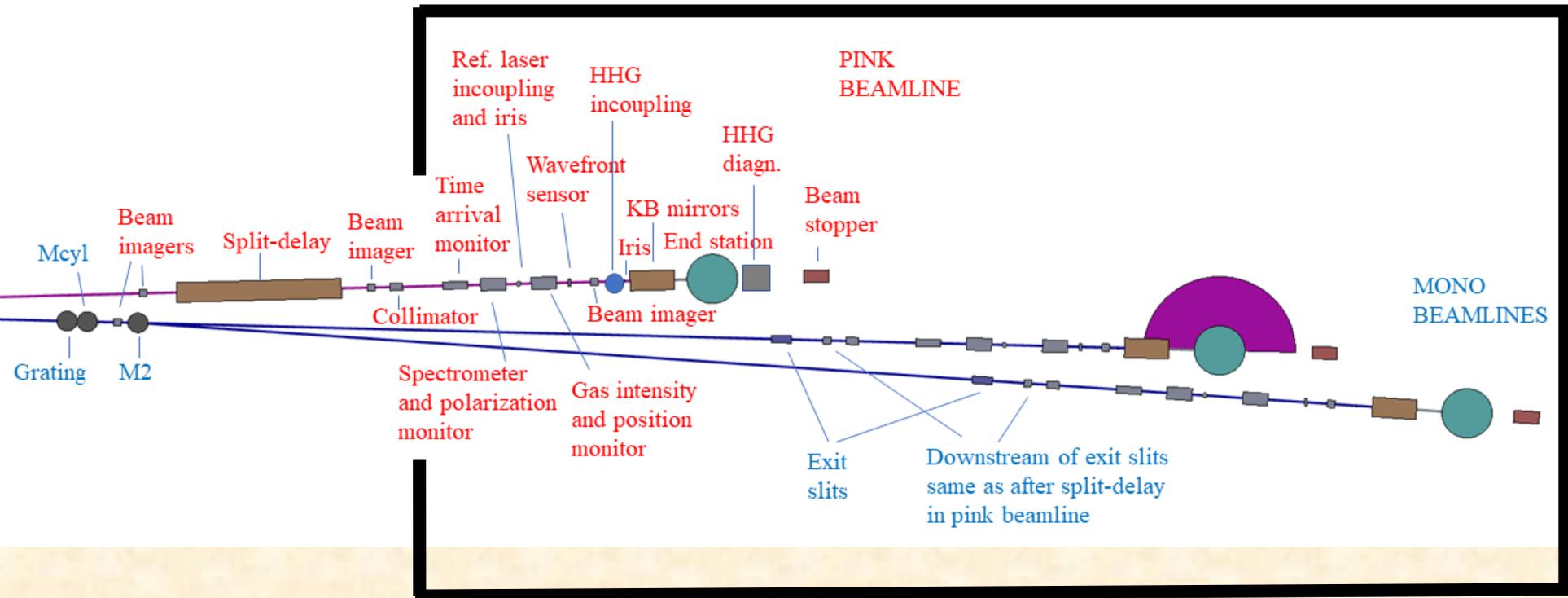
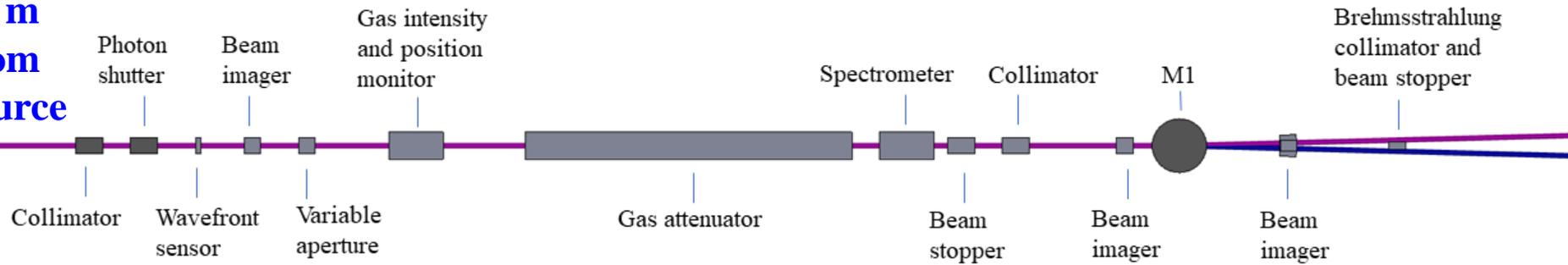


Grating type and mount



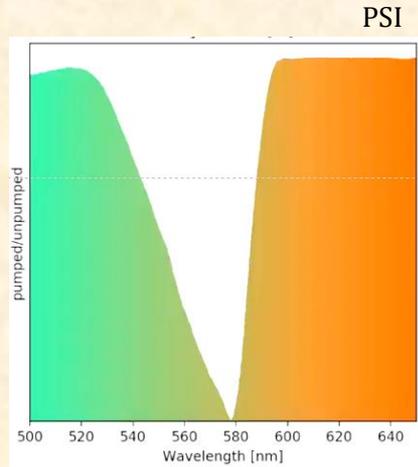
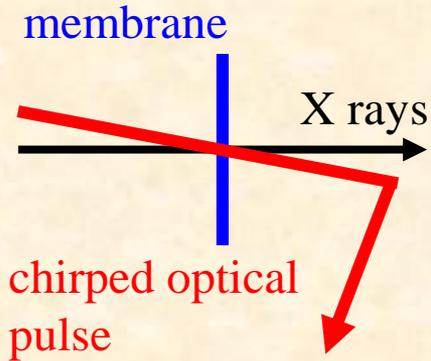
Overview of instruments and detectors

54 m
from
source

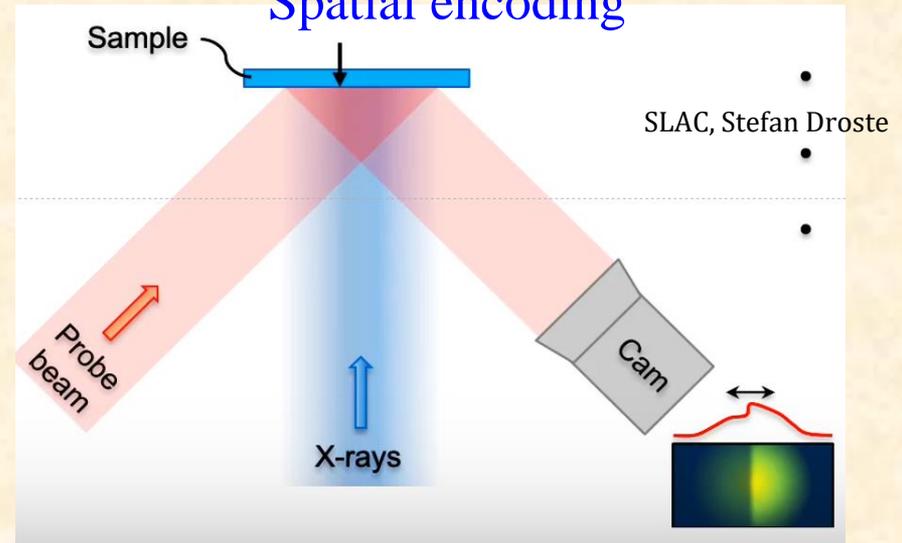


Temporal X-ray pulse characterization

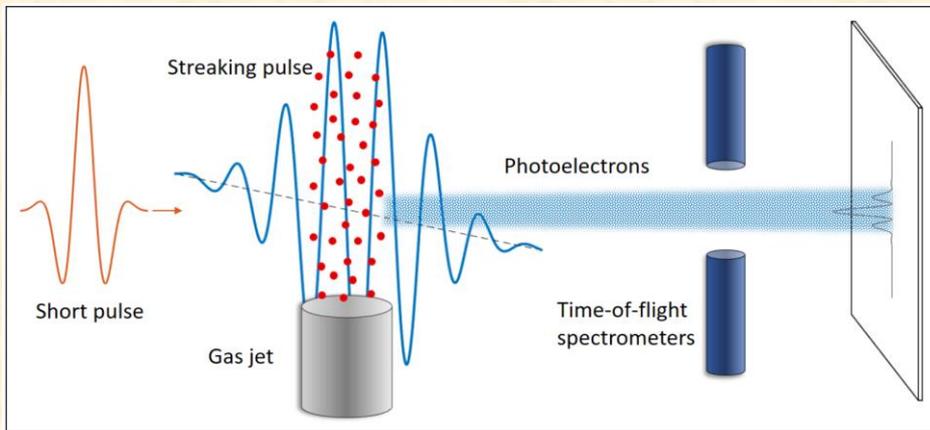
Spectral encoding



Spatial encoding

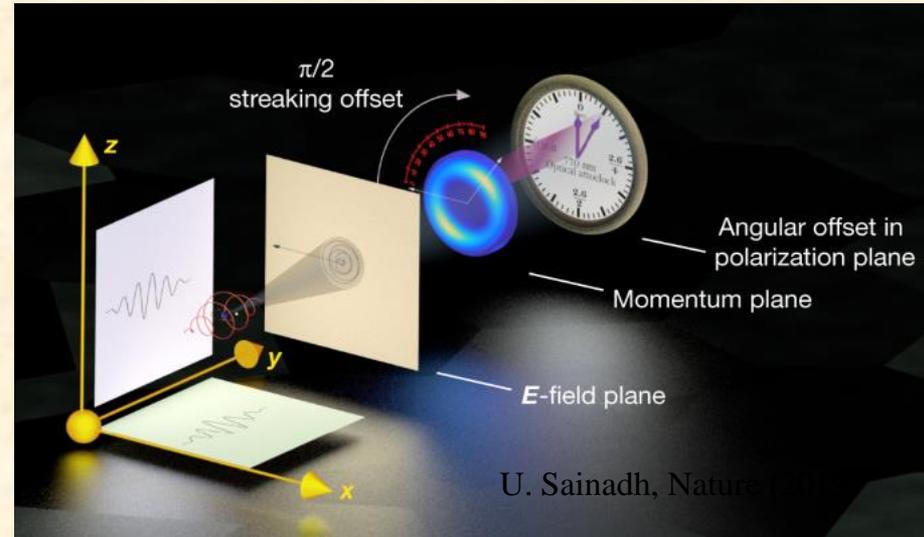


Linear THz streaking



UU, G. Shamuilov

Angular IR streaking



U. Sainadh, Nature

Comparison of methods

Method	Arrival time, accuracy (fs)	Pulse duration, resolution (fs)	Measurement interval (ps)	Double FEL pulses, accuracy (fs)
Spatial encoding	1.5	no	2	no
Spectral encoding	4.5	no	3	no
Spectrogram	< 1	no	~4	no
THz streaking	~10	~10 fs	0.5	25
mid-IR streaking	~1	0.25 (0.1 for double pulses)	0.34	1
VMI streaking*	N/A	~ 0.1	?	?

- Mid-IR angular streaking is a very complicated technique
- But only mid-IR angular streaking measurement capabilities comply with all the XLS science requirements
- In the baseline design, we could start with THz streaking that is simpler.